

IN THE CLAIMS:

1. (Cancelled)

2. (Cancelled)

3. (Cancelled)

4. (Cancelled)

5. (Cancelled)

6. (Cancelled)

7. (Cancelled)

8. (Cancelled)

9. (Cancelled)

10. (Cancelled)

11. (Cancelled)

12. (Cancelled)

13. (Cancelled)

14. (Cancelled)

15. (New) A radiation-sensitive resin composition comprising:

water,

a water-soluble resin dissolved in the water,

a water-insoluble or sparingly water-soluble acid former dispersed in the water,

said acid former generating an acid when irradiated with activation energy,

a sensitizer, dispersed in the water, for sensitizing the acid generation by the acid former, and

an acid-reactive insolubilizing agent dissolved or dispersed in the water for converting the water-soluble resin into an insoluble form in the presence of said acid.

16. (New) The composition as recited in claim 15, further comprising a compound having at least one radically polymerizable unsaturated bond and dissolved or dispersed in the water.

17. (New) The composition as recited in claim 15, wherein said acid-reactive insolubilizing agent is an N-methylolated or N-alkoxymethylated nitrogen-containing compound, a hydroxymethylated phenol derivative or a resol resin.

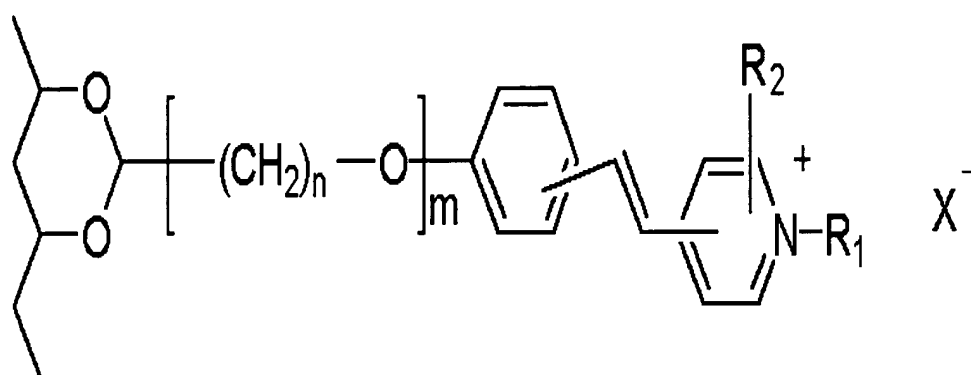
18. (New) The composition as recited in claim 15, wherein said acid-reactive insolubilizing agent is a compound having at least one epoxy group, oxetane group, vinyloxy group, isopropenyloxy group or orthoester group.

19. (New) The composition as recited in claim 15, wherein said acid-reactive insolubilizing agent has at least one formyl group.

20. (New) The composition as recited in claim 15, further comprising an aqueous emulsion of a hydrophobic polymer.

21. (New) The composition as recited in claim 15, further comprising a water-soluble, photo-insolubilizable resin.

22. (New) The composition as recited in claim 21, wherein said water-soluble, photo-insolubilizable resin is a photo-crosslinkable polyvinyl alcohol containing a styrylpyridinium group represented by the following formula (1):



wherein R_1 represents a hydrogen atom, an alkyl group or an aralkyl group, R_2 represents a hydrogen atom or a lower alkyl group, X^- represents a halogen ion, a phosphate ion, a p-toluenesulfonate ion or a mixture of these anions, m is a number of 0 or 1 and n is an integer of 1 to 6.

23. (New) The composition as recited in claim 21, wherein said water-soluble, photo-insolubilizable resin comprises poly(vinyl alcohol), casein or gelatin, and a water-soluble diazo resin or a dichromate.

24. (New) The composition as recited in claim 15, wherein said acid-reactive insolubilizing agent is present in an amount of 5 to 1,000 parts by weight per 100 parts by weight of said water-soluble resin, said acid former is present in an amount of 1 to 100 parts by weight per 100 parts by weight of said acid-reactive insolubilizing agent, and said sensitizer is present in an amount of 5 to 100 parts by weight per 100 parts by weight of said acid former.

25. (New) The composition as recited in claim 15, wherein each of said acid former and sensitizer has an average particle diameter of 1.5 μm or less.

26. (New) A radiation-sensitive resin film obtained by drying a layer of the composition according to claim 15.

27. (New) Use of the resin film of claim 26 for a screen printing process.

28. (New) A pattern forming method comprising the steps of:

irradiating a radiation sensitive resin film according to claim 26 with activation energy, and

developing the irradiated film with water.

29. (New) A pattern forming method as recited in claim 28, further comprising heating the irradiated film before said developing with water.

30. (New) The composition as recited in claim 15, wherein each of said acid former and sensitizer is in the form of solid particles dispersed in the water.